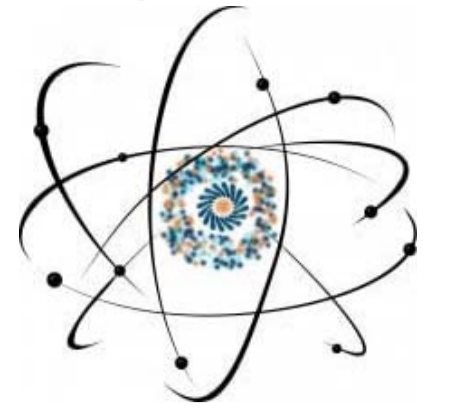


CdS nanocrystals formed in amorphous GeS₂:Cd films by photoenhanced diffusion



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INTRODUCTION

II–VI semiconductor nanocrystals (NCs), in particular CdS, belong to the most widely studied materials of this class produced by colloidal synthesis [1,2], diffusion-limited growth in glass matrices [3], Langmuir-Blodgett technique [4], sequential ion implantation [5] etc. These techniques enable one to obtain ensembles of NCs dispersed in a liquid or an amorphous dielectric matrix. Here we report on a localised formation of CdS NCs in Cd-doped amorphous GeS₂ films due to a strong enhancement of diffusion in the amorphous film induced by bandgap laser light illumination. A similar technique was used to obtain CdS NCs in amorphous As₂S₃ [6] as well as other II–VI NCs in non-crystalline arsenic chalcogenides [7–9].

EXPERIMENTAL

1–2 mm thick Cd-doped (the nominal Cd content up to 10 at.%) GeS₂ films were grown by thermal evaporation technique on silicate glass and silicon substrates. The film surface morphology was checked by Agilent AFM 5420 operating in intermittent contact mode. Micro-Raman measurements were performed at room temperature using a Horiba LabRAM spectrometer with a CCD camera. The excitation was provided by a Cobold Fandango solid-state laser (514.7 nm). The instrumental resolution was in all cases better than 2.5 cm⁻¹.

RESULTS AND DISCUSSION

ATOMIC FORCE MICROSCOPY

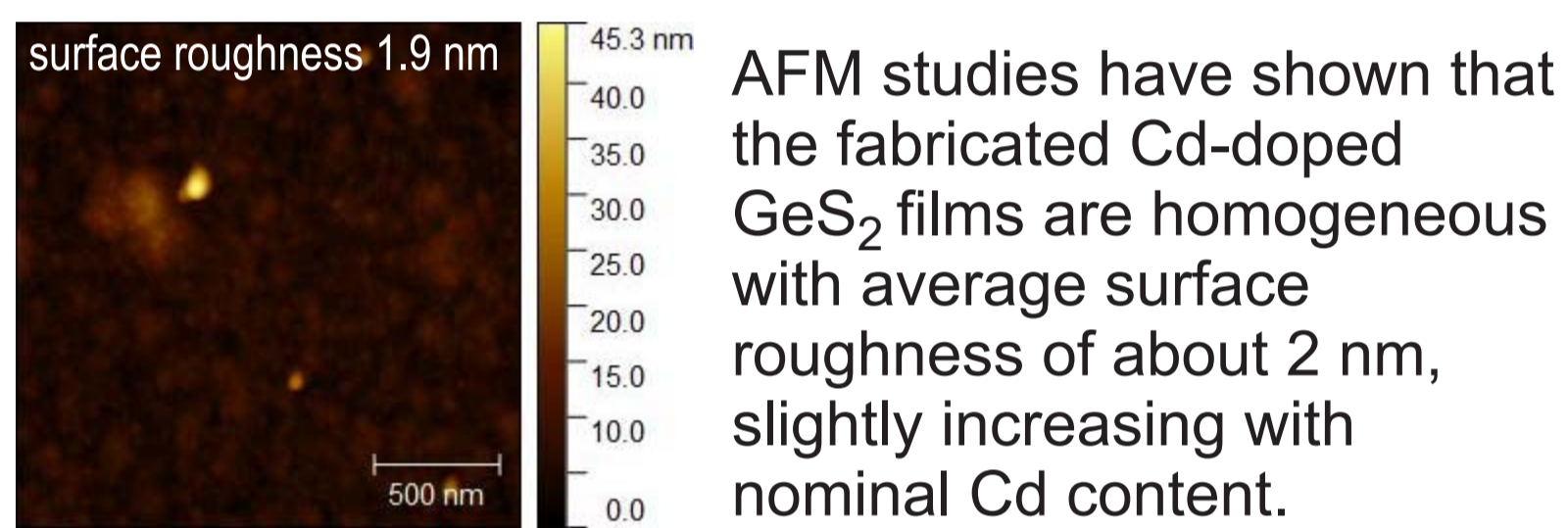


Fig. 1. AFM surface topography of a GeS₂ film

RAMAN SPECTROSCOPY

The reason for the pit formation on the GeS₂ film surface is a drastic non-thermal photoinduced drop of the film viscosity (photosoftening) resulting in a radial mass transfer from the laser spot. Similar effects were observed for As₂S₃ [6, 9] and As₂Se₃ [7–9].

For Cd-doped (10 %) GeS₂ films the Raman spectra depend on P_{exc}. At low P_{exc} they are similar to the undoped films (typical amorphous GeS₂). At high P_{exc} suddenly a sharp peak slightly below 300 cm⁻¹ and a weaker and broader band at a doubled frequency emerge (highlighted in Fig. 4 by yellow bars). Moreover, the peaks remain after P_{exc} is reduced again showing that the transformation was irreversible.

We relate these peaks to LO and 2LO phonons of CdS NCs formed in the GeS₂ film due to a strong enhancement of diffusion (photosoftening) enabling Cd and S atoms to assemble in NCs similarly to how it is known for Cd-doped As₂S₃ [6] and As₂Se₃ [7,8].

The CdS LO and 2LO frequencies are below then expected for bulk CdS. This can be related to phonon confinement [11], strain [11], or flexoelectric effect [8]. The first factor is excluded because of a too high downward shift, the role of two others is discussed.

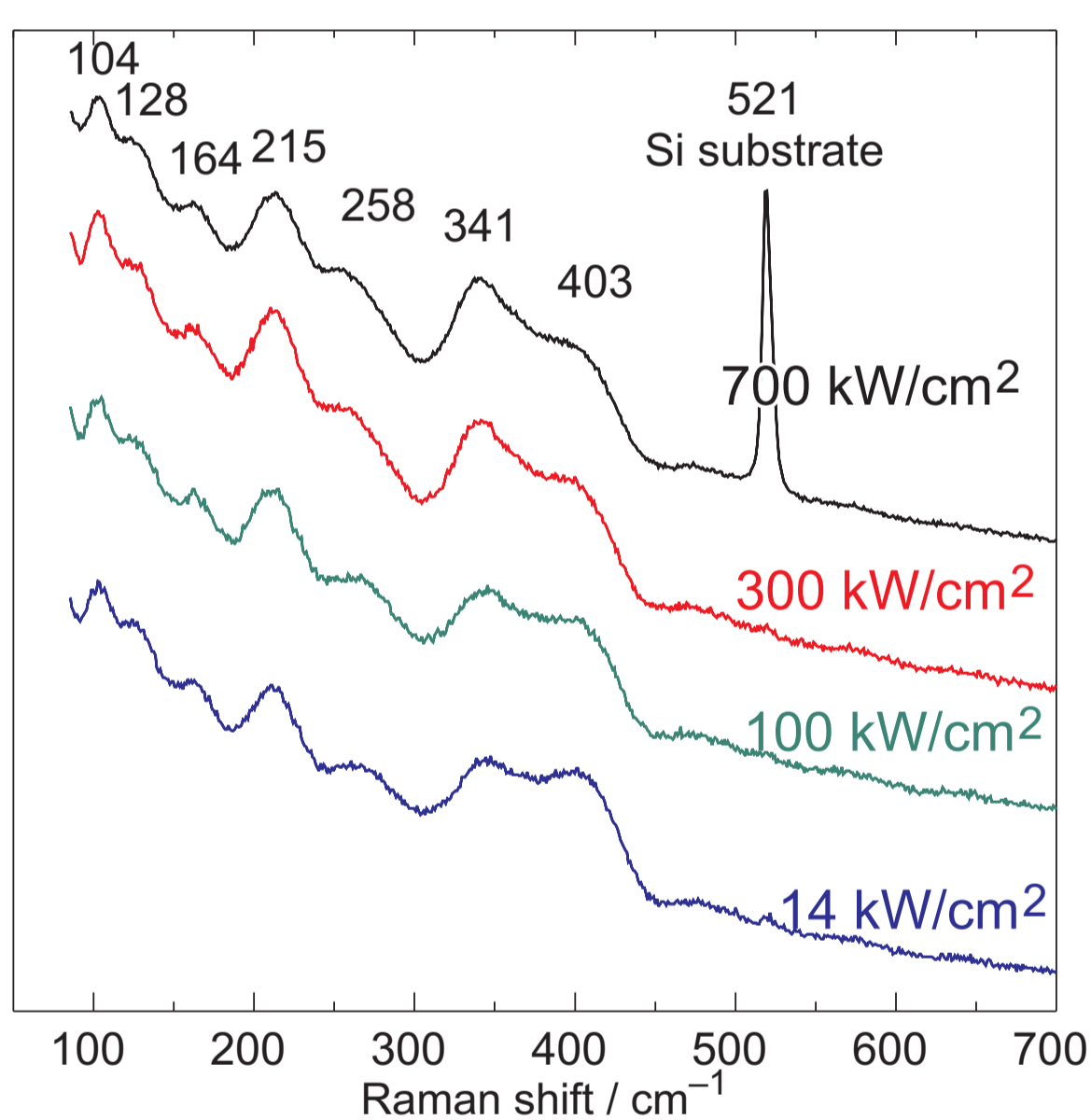


Fig. 2. Raman spectra of an undoped GeS₂ film.

Raman spectra of GeS₂ films exhibit a series of broad features in the interval 100–500 cm⁻¹, typical for amorphous GeS₂ [10]. The spectra do not vary with the laser power density P_{exc}. The peak at 521 cm⁻¹ from the silicon substrate appears at the highest because at such P_{exc} a pit is formed on the film surface.

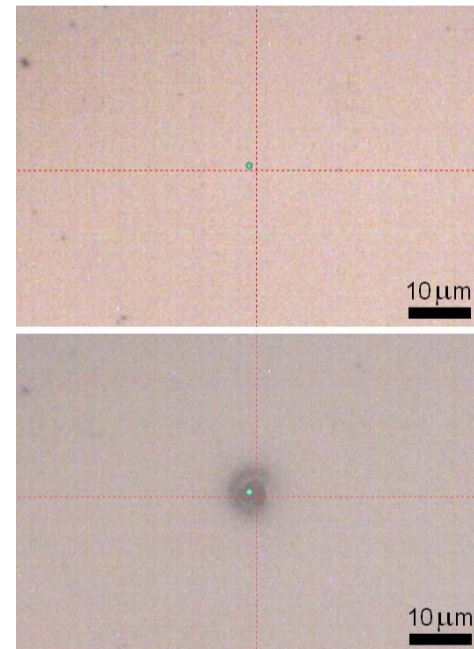


Fig. 3. GeS₂ film surface before and after illumination (700 kW/cm², 20 s).

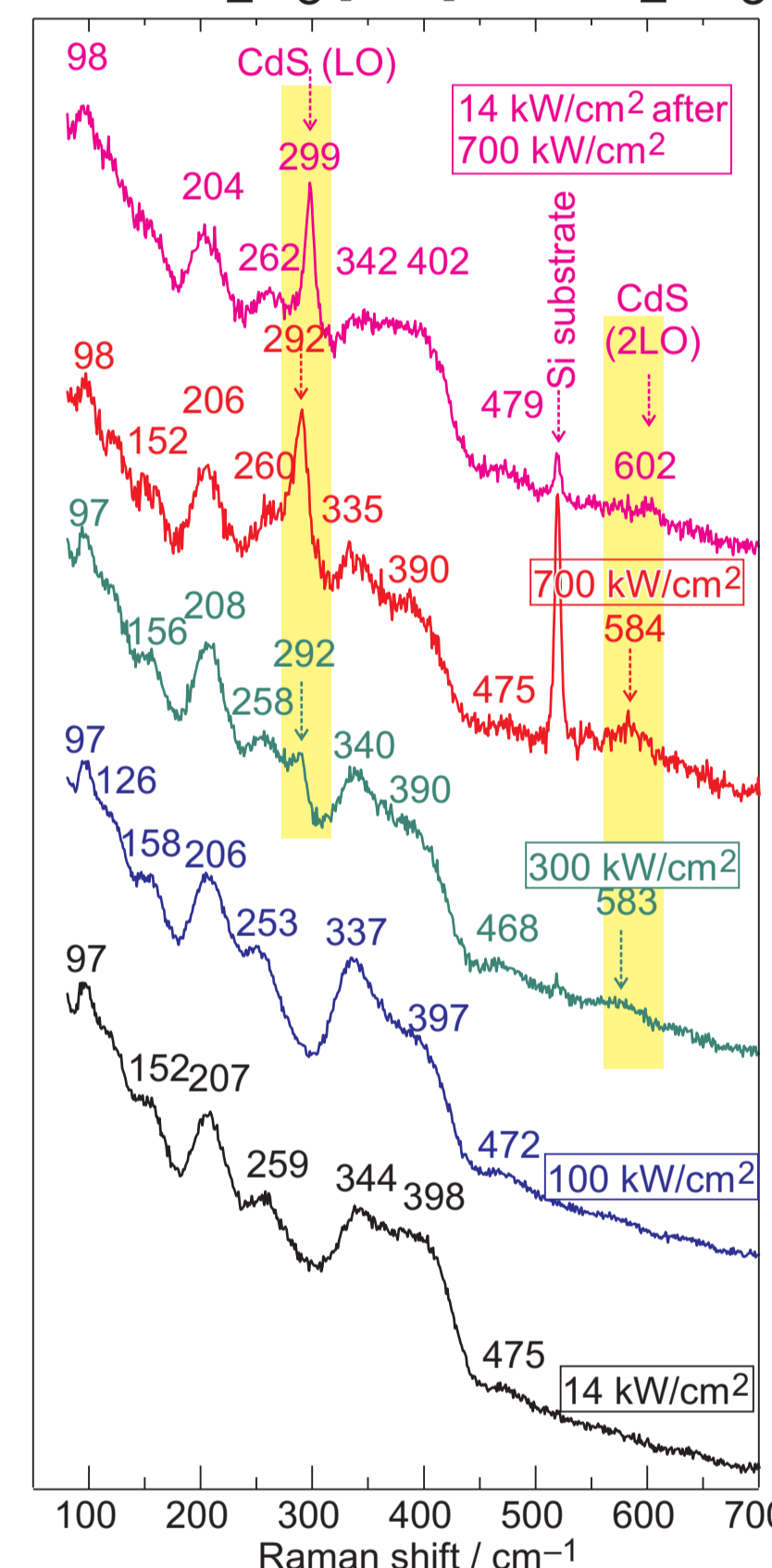


Fig. 4. Raman spectra of a Cd-doped (10 at. %) GeS₂ film at different P_{exc}.

CONCLUSIONS

- Good-quality amorphous films of GeS₂:Cd with surface roughness below 2 nm were obtained by thermal evaporation.
- At P_{exc} > 300 mW/cm² a dip is formed in the film surface due to a drastic non-thermal photosoftening of the film and mass transfer from the laser spot.
- With increasing P_{exc} for Cd-doped films, CdS NCs are formed due to photoenhanced diffusion.
- The observed downward shift of the CdS NC LO and 2LO phonon frequencies can be explained by tensile strain and/or flexoelectric effect.

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